

TELIC

RECOMMENDED PROCESS FOR TELIC PHOTOMASK BLANKS

PROCESS FOR: Gobo Blanks Coated with 3000Å Al & 5300Å AZ 1500 Photoresist

<u>Process Step</u>	<u>Chemical</u>	<u>Process Parameter</u>
Exposure	Broadband UV 25 mJ/cm ²	7 sec.
Development	AZ 300 MIF	30 sec.
Rinse	DI Water	40 sec.
Etching	Cyantek AL-12S Aluminum Etch	7 min. 30 sec.
Rinse	DI Water	40 sec.
Resist Strip	Cyantek RS-120	5 min. @ 50° C
Final Clean	Cyantek Nanostrip	3 min.
Rinse	DI Water	40 sec.

PROCESS FOR: Mask Blanks Coated with 1000Å Low Reflective Chrome & 5300Å AZ 1500 Photoresist

<u>Process Step</u>	<u>Chemical</u>	<u>Process Parameter</u>
Exposure	Broadband UV 25 mJ/cm ²	7 sec.
Development	AZ 300 MIF	30 sec.
Rinse	DI Water	40 sec.
Etching	MCT CEP-200 / Cyantek CR-9	60 sec.
Rinse	DI Water	40 sec.
Resist Strip	MCT PRS-100 / Cyantek RS-120	5 min. @ 50° C
Final Clean	Cyantek Nanostrip	3 min.
Rinse	DI Water	40 sec.

RECOMMENDED VENDORS FOR MASK PROCESSING CHEMISTRY

Microchrome Technology
1605 Remunda Lane
San Jose, CA 95112
Tel: 408.452.5500
Fax: 408.452.5505

Cyantek Corp.
3055 Osgood Court
Fremont, CA 94539
Tel: 510.651.3341
Fax: 510.651.3398

Telic Company 24832 Avenue Rockefeller, Valencia CA, 91355, USA
T: 661.702.8603 F: 661.257.6802 TF: 661.866.TelicCo
E: MKennedy@TelicCo.com www.TelicCompany.com